Niobium Nb Sputtering Targets



Advanced Engineering Materials



Applications

- Optical films
- Filters
- Fiber optics
- Architectural glass
- Wear coatings

Features

- High purity
- Grain refinement

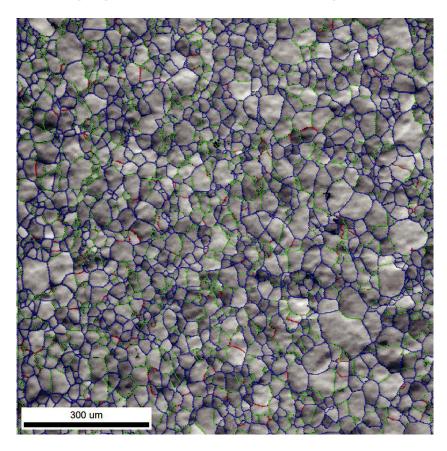
Manufacturing Process

- Refining
 Multiple step electron beam melting
- Rolled and annealed
- Cleaning and final packaging
- Cleaned for use in vacuum
 Protection from environmental contaminants
- Protection during shipment

Options

- 99.95% minimum purity (excluding Ta)
- Planar circular targets up to 20" (500 mm) diameter
- Planar tiles up to 70" (1800 mm) length and width for larger target configurations
- Smaller sizes also available for R&D applications
- · Sputtering target bonding service

Average grain size <50µm (50X magnification)



Specifications

Typical Analysis - 99.95% (3N5) Purity Metallic Impurities, ppm by weight

Si	CI	Fe	Cu	Pd	Ag	Hf	Та	W	Zr	Мо
<5	<5	<5	<5	<5	<10	<5	<450	<50	<5	<5

Non-Metallic Impurities, ppm by weight

С	н	0	Ν
<50	<10	<100	<10

Theoretical Density	8.57 g/cm₃
Average Grain Size	<50 μm
Electrical Resistivity	152 nΩ [•] m
Thermal Conductivity	53.7 W/m [•] K
Melting Point	2468°C
Appearance	Grey, metallic

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